

HEIDELBERG DWL 66

 Villach

BRIEF DESCRIPTION

This Laser lithography system is a highly versatile, high-resolution pattern generator for direct writing and low-volume mask making.

RESEARCH SERVICES

- 200 mm down 1 cm² substrate size
- i-line band (375 nm) for negative and positive resist exposures
- grayscale mode for 2.5D patterning
- minimum feature size 1 μm

METHODS & EXPERTISE ON THE RESEARCH INFRASTRUCTURE

The Heidelberg DWL 66 is used for R&D in microelectronics, MEMS, microfluidics, sensors, non-standard substrates and advanced packaging and any academic application that requires microstructure fabrication.

CONTACT

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